

ABSTRACT OF THE DISCLOSURE

In a method of fabricating a protective film, a vacuum ultraviolet radiation CVD (Chemical Vapor Deposition) system is provided. The system includes a vacuum ultraviolet rays generator, a reactor provided with a platform for supporting a substrate, a heat retainer provided on the platform, and a window separating the vacuum ultraviolet rays generator from the reactor. Then, an organic stock gas is fed from a gas feeder into the reactor while retaining temperature of the substrate at a low temperature with the heat retainer. Simultaneously, the reactor is irradiated with vacuum ultraviolet rays from the vacuum ultraviolet rays generator through the window.